

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant:	Horning et al.	Attorney Docket No.	H16-16009 H000-1-1200
Serial No.:	09/873,931	Group Art Unit:	2814
Filing Date:	June 4, 2001	Examiner:	RAO, Shrinivas
Title:	APPLICATIONS OF A STRAIN-COMPENSATED HEAVILY DOPED ETCH STOP FOR SILICON STRUCTURE FORMATION		

**RESPONSE TO FINAL OFFICE ACTION**

**TO THE COMMISSIONER OF PATENTS:**

**AMENDMENT AND RESPONSE**